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				First Named Inventor	Hai Deng		
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Sheet	2	of	2	Attorney Docket Number	42P17681		

NON PATENT LITERATURE DOCUMENTS							
Examiner Initials*	Cite No.'	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-Issue number(s), publisher, city and/or country where published.	T*				
dhu		MORRIS, et al. METHOD OF FABRICATION OF LOW DIELECTRIC CONSTANT POROUS METAL SILICATE FILMS. U.S. Patent Application No. 10/323,988, Filed 12/17/2002, 23 pages.	:				
dha dha		ZHENGBAO WANG, et al., Pure Silica Zeolite Films as Low-k Dielectrics by Spin-On of Nanoparticle Suspensions, Advanced Materials 2001, No. 19, October 2, pp.1463-1466	:				
dlen		ZHENGBAO WANG, et al., Silica Zeolite Low-k Dielectric Films, Department of Chemical and Environmental Engineering, University of California, Riverside, 15 pages.	line				
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^{*}Examinor: Initial it reference considered, whether or not cliation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication.

Based on PTC/SB/08B (08-03) as modified by Blakely, Solokoff, Teylor & Zelman (w/) 08/11/2003. Send To: Commissioner for Patenta. P.O. Box 1450, Alexandria, VA 22313-1450

^{&#}x27;Applicant's unique citation designation number. 'Applicant is to place a check mark here if English tanguage Translation is attached.